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| APPLICATION NO. | FILING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. |
|--------------------|-------------------|----------------------|-------------------------|------------------|
| 10/692,255 | 10/22/2003 | Terry Lines | 100-14310 (P04927-C1) | 9418 |
| 33402 | 7590 02/17/2005 | | EXAMINER | |
| LAW OFFIC | ES OF MARK C. PIO | LEE, EUGENE | | |
| P.O. BOX 300 | | | | - V |
| PETALUMA, CA 94953 | | | ART UNIT | PAPER NUMBER |
| | | • | 2815 | |
| | | | DATE MAILED: 02/17/2005 | |

Please find below and/or attached an Office communication concerning this application or proceeding.

| | | | | H.H | | | |
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| | | Application No. | Applicant(s) | | | | |
| Office Action Servers | | 10/692,255 | LINES, TERRY | | | | |
| | Office Action Summary | Examiner | Art Unit | | | | |
| | | Eugene Lee | 2815 | | | | |
| Period for | The MAILING DATE of this communication app Reply | pears on the cover sheet with the c | correspondence address | s | | | |
| THE M - Extens after SI - If the p - If NO p - Failure Any rep earned | RTENED STATUTORY PERIOD FOR REPL AILING DATE OF THIS COMMUNICATION. ions of time may be available under the provisions of 37 CFR 1.1 X (6) MONTHS from the mailing date of this communication. eriod for reply specified above is less than thirty (30) days, a repleriod for reply is specified above, the maximum statutory period to reply within the set or extended period for reply will, by statute ply received by the Office later than three months after the mailing patent term adjustment. See 37 CFR 1.704(b). | 136(a). In no event, however, may a reply be tin by within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDONE | nely filed s will be considered timely. the mailing date of this commur D (35 U.S.C. § 133). | nication. | | | |
| Status | | | | | | | |
| 1)⊠ F | Responsive to communication(s) filed on <u>13 E</u> | December 2004. | | | | | |
| , | ☐ This action is FINAL. 2b)☐ This action is non-final. | | | | | | |
| · — | | | | | | | |
| C | closed in accordance with the practice under I | Ex parte Quayle, 1935 C.D. 11, 4 | 53 O.G. 213: | | | | |
| Dispositio | n of Claims | | | | | | |
| | I)⊠ Claim(s) <u>1-9</u> is/are pending in the application. | | | | | | |
| | 4a) Of the above claim(s) is/are withdrawn from consideration. | | | | | | |
| • | Claim(s) 3-9 is/are allowed. | | | | | | |
| | Claim(s) 1 and 2 is/are rejected. | | | | | | |
| | | | | | | | |
| | | or oreal or requirement. | | | | | |
| Applicatio | | | | | | | |
| • | the specification is objected to by the Examine | | in an | | | | |
| 10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner. | | | | | | | |
| | Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a). Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). | | | | | | |
| | the oath or declaration is objected to by the E | | | | | | |
| ,— | | | | | | | |
| - | nder 35 U.S.C. § 119 | | | | | | |
| a)[| cknowledgment is made of a claim for foreign All b) Some * c) None of: I. Certified copies of the priority documen | |)-(d) or (f). | • • . | | | |
| 2 | 2. Certified copies of the priority documents have been received in Application No | | | | | | |
| ; | 3. Copies of the certified copies of the price | ority documents have been receiv | ed in this National Stag | је | | | |
| | application from the International Bureau (PCT Rule 17.2(a)). | | | | | | |
| * Se | ee the attached detailed Office action for a lis | t of the certified copies not receive | ed. | | | | |
| | | | | | | | |
| Attachment(| s) | | | | | | |
| | of References Cited (PTO-892) | 4) Interview Summary Paper No(s)/Mail D | | | | | |
| | of Draftsperson's Patent Drawing Review (PTO-948) ation Disclosure Statement(s) (PTO-1449 or PTO/SB/08 | | Patent Application (PTO-152 |) | | | |
| | No(s)/Mail Date | 6) 🔲 Other: | | | | | |

DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1 and 2 are rejected under 35 U.S.C. 103(a) as being unpatentable over Klein 4,205,330 in view of Takagi 4,003,071. Klein discloses (see, for example, Fig _4) a MOSFET circuit (semiconductor circuit) comprising a depletion mode device (first transistor) wherein the depletion mode device comprises a first semiconductor region, source 37, drain 38, region (first channel) 30a, first gate oxide 29a, and gate 34; an enhancement device (second transistor) wherein the enhancement device comprises a second semiconductor region, source 35, drain 36, region (second channel) 30, second gate oxide 29, and gate 32.

Klein does not disclose the thickness of the layer of first gate oxide being substantially less than the thickness of the layer of second gate oxide. However, Takagi discloses (see, for example, FIG. 6A) a semiconductor device comprising a depletion mode transistor 63 with a gate insulating film 66, and an enhancement-type transistor 62 with a gate insulating film 65. The thickness of the gate insulating film 66 of the depletion mode transistor is substantially less than the thickness of the gate insulating layer 65 of the enhancement mode transistor. In column 8, lines 17-34, Takagi discloses that gate insulating layer of the depletion mode transistor permits the formation of the impurity diffused layer whereas the gate insulating layer of the enhancement mode transistor prevents it. Therefore, it would have been obvious to one of ordinary skill in the

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art to have the thickness of the layer of first gate oxide being substantially less than the thickness of the layer of second gate oxide in order to only form the layers necessary in the formation of an enhancement and depletion mode transistor, and to save in manufacturing steps.

Regarding the limitation "the first channel having a first dopant concentration" and the limitation "the second channel having a second dopant concentration", see column 4, lines 7-11 wherein Klein discloses phosphorous, an n-type impurity, implanted to create the phosphorous doped region 30a, 30.

Regarding the limitation "the first transistor conducting more than leakage current when the gate, the source, and the first semiconductor region are connected to a same potential (which is a depletion device according to applicant's specification on page 1)" and the limitation "the second transistor being substantially non-conductive when the gate of the second transistor, the source of the second transistor, and the second semiconductor region are connected to a same potential (enhancement device)", see, for example, column 4, lines 10-11 wherein Klein discloses the depletion mode device with region 30a and the enhancement device with region 30.

Regarding claim 2, see, for example, column 4, lines 11-18, wherein Klein discloses the phosphorus implant at 30 will only have a small effect in the region of the enhancement type device and the region 30a of the depletion type device will produce a junction and an n-type surface channel which is more heavily doped than the substrate.

Allowable Subject Matter

3. Claims 3 thru 9 are allowed. The following is a statement of reasons for the indication of allowable subject matter: The references of record, either singularly or in combination, do not

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teach or suggest at least a semiconductor circuit comprising: a third transistor formed in the semiconductor material, the third transistor having a third channel and a layer of third gate oxide formed over the third channel, the third channel having a third channel length and a third dopant concentration, the layer of third gate oxide having a thickness, the third transistor being substantially non-conductive when zero volts are applied to the gate, the thickness of the layer of third gate oxide being substantially equal to the thickness of the layer of first gate oxide.

Response to Arguments

4. Applicant's arguments with respect to claims 1-9 have been considered but are moot in view of the new ground(s) of rejection.

Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event,

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however, will the statutory period for reply expire later than SIX MONTHS from the date of this

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final action.

INFORMATION ON HOW TO CONTACT THE USPTO

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Eugene Lee whose telephone number is 571-272-1733. The

examiner can normally be reached on M-F 8-5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Tom Thomas can be reached on 571-272-1664. The fax phone number for the

organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Eugene Lee

February 11, 2005

TOM THOMAS
SUPERVISORY PATENT EXAMINER